

CNM Short Course D - Thin Film Deposition Overview

Time: 8:30 – 12:00

Date: Thursday, April 23

Location: Bldg. 440, Room A106

Instructor: Liliana Stan

Description: This course is designed as an introduction to fundamental concepts and operating principles for the deposition of thin films by physical vapor deposition or chemical methods, providing a broad overview of thin film deposition methods, their advantages and limitations. Understanding that all methods have their specific limitations and involve compromises with respect to process specifics and substrate material, helps determining the methods that are suitable for achieving the expected film properties. Deposition methods that are available at the Center for Nanoscale Materials (CNM) - sputtering, evaporation, ALD, and CVD - will be discussed in more detail.

Max Attendees: 12